

Contents

PREFACE

xv

PART I: FUNDAMENTALS AND MODELING

*THE MATHEMATICAL MODELLING OF TRANSPORT PHENOMENA IN NON-TRANSFERRED PLASMA SYSTEMS: ACCOMPLISHMENTS AND UNRESOLVED PROBLEMS A.H. Dilawari and J. Szekely	3
THEORETICAL PREDICTION OF THE EFFECT OF COIL CON- FIGURATION ON GAS MIXING IN AN INDUCTIVELY COUPLED PLASMA TORCH John W. McKelliget and Nagy El-Kaddah	21
A KINETIC MODEL FOR LOW-PRESSURE RF DISCHARGE ETCHING OF SILICON USING SF ₆ Ajit P. Paranjpe, George Kychakoff, and Sidney A. Self	29
ESTIMATION OF ION IMPACT ENERGIES AND ELECTRODE SELF- BIAS VOLTAGE IN CAPACITIVE RF DISCHARGES S.E. Savas	35
*A CRITICAL ANALYSIS OF PROPOSED PLASMA JET MODELS TO PREDICT TEMPERATURE AND VELOCITY PROFILES Daniel Y.C. Wei, Bakhtier Farouk, and Diran Apelian	41
MODELING TURBULENCE IN A THERMAL PLASMA REACTOR D.J. Varacalle, Jr., L.D. Reynolds, and C.B. Shaw, Jr.	49
A METHOD FOR NON-INTRUSIVELY DETERMINING ION IMPACT CURRENT DENSITY AND ENERGY DISTRIBUTION IN CAPACI- TIVELY COUPLED RF PLASMAS S.E. Savas	61
A MATHEMATICAL REPRESENTATION OF THE ION NITRIDING PROCESS J-L. Marchand, D. Ablitzer, J. Szekely, H. Michel, and M. Gantois	67
EFFECT OF PARTICLE LOADING ON DC PLASMA JET PROFILE DURING LOW PRESSURE PLASMA DEPOSITION Daniel Y.C. Wei, Diran Apelian, and Bakhtier Farouk	77
MELTING PHENOMENA OF SEVERAL NICKEL BASE ALLOYS IN A PLASMA JET OPERATING AT LOW PRESSURE Ronald W. Smith and Diran Apelian	89

*Invited Paper

PART II: DIAGNOSTICS

*TEMPERATURE MEASUREMENTS IN ATMOSPHERIC SPRAYING PLASMA JETS: GAS AND PARTICLES IN FLIGHT P. Fauchais, J.F. Coudert, M. Vardelle, and A. Vardelle	101
A SPECTROSCOPIC STUDY OF THE CONDITIONS REQUIRED FOR PLASMA ETCHING OF ALUMINUM IN BCl_3 AND Cl_2 PLASMAS J.A. Cairns, R. Smailes, D.C.W. Blaikley, P.M. Banks, G. Hancock, I. Hussla, and W. Katzschnner	121
SIMULTANEOUS MEASUREMENT OF PARTICLE SIZE AND TEMPERATURE IN A PLASMA TORCH J.R. Fincke, C.L. Jeffery, and S.B. Englert	127
LASER INDUCED FLUORESCENCE AND OPTICAL EMISSION STUDIES OF FLUOROCARBON PLASMAS J.P. Booth, G. Hancock, N.D. Perry, D.C.W. Blaikley, J.A. Cairns, and R. Smailes	135
THE POTENTIAL OF INFRARED VIDEO THERMOGRAPHY FOR CONTROL OF ARC-PLASMA SPRAY FABRICATIONS D. Harris and M. Kelly	141
THE APPLICATION OF PLANAR LASER-INDUCED FLUORESCENCE AS A DIAGNOSTIC IN PLASMA PROCESSING J.K. Partin, J.R. Fincke, C.L. Jeffery, S.C. Snyder, and J.A. Batdorf	149
CHARACTERIZATION OF PLASMA-DEPOSITED AMORPHOUS CARBON FILMS Wen L. Hsu, G.W. Foltz, F.A. Greulich, K.F. McCarty, G.J. Thomas, P.F. Green, and B.L. Doyle	155
LASER/OPTICAL DIAGNOSTIC TECHNIQUES FOR PLASMA MATERIALS PROCESSING Ward C. Roman	161
AN EXPERIMENTAL METHOD FOR SPECIES CONCENTRATION MEASUREMENTS IN A WELDING ARC USING LASER-INDUCED FLUORESCENCE S.C. Snyder, C.B. Shaw, Jr., and C.L. Shull	177
DIAGNOSTIC TECHNIQUES FOR THERMAL PLASMAS Sidney A. Self	183
PLASMA DIAGNOSTICS FOR A LOW-PRESSURE PLASMA SPRAY DEPOSITION SYSTEM Suzanne H. Weissman, Mark F. Smith, and William B. Chambers	197
IN-SITU MONITORING OF ELECTRICAL PARAMETERS FOR DRY ETCHING J. Ignacio Ulacia and James P. McVittie	203

*Invited Paper

SPATIALLY-RESOLVED EMISSION PROFILES OF PARALLEL PLATE RF GLOW DISCHARGES Richard M. Roth	209
PART III: PLASMA PROCESSING OF ELECTRONIC MATERIALS	
PLASMA CHEMICAL ASPECTS OF MAGNETRON ION ETCHING WITH CF_4/O_2 AND CF_4/H_2 A.A. Bright, S. Kaushik, and G.S. Oehrlein	217
LARGE AREA ELECTRON BEAM ENHANCED REACTIVE ETCHING OF SiO_2 P. Kirk Boyer, Tim Verhey, and Jorge J. Rocca	223
MECHANISM OF THE SLOW-DOWN OF THE SILICON ETCH RATE BY A FLUOROCARBON OVERLAYER IN CF_4/H_2 REACTIVE ETCHING OF SILICON Gottlieb S. Oehrlein, Steve W. Robey, and Mark A. Jaso	229
GROWTH AND CHARACTERIZATION OF EPITAXIAL GaAs DEPOSITED BY PLASMA-ENHANCED METAL-ORGANIC CHEMICAL VAPOR DEPOSITION A.D. Huelsman, E. Yoon, and R. Reif	235
A STUDY OF TITANIUM SILICIDE POLYCID ETCING S.M. Bobbio, Y.S. Ho, and T. Lopez	243
PULSED INDUCTIVE PLASMA PROCESSING FOR AMORPHOUS THIN FILM FORMATION Kenji Ebihara and Sadao Maeda	249
A NEW METHOD FOR REAL-TIME PLASMA ETCH PROCESS CONTROL: CORRELATION OF CONTACT RESISTANCE WITH NONDESTRUCTIVE MODULATED REFLECTANCE Alp Malazgirt and W. Lee Smith	255
PHOTORESIST STRIPPING USING A REMOTE PLASMA: CHEMICAL AND TRANSPORT EFFECTS Lee M. Loewenstein, Craig H. Huffman, and Cecil J. Davis	267
THE INFLUENCE OF MAGNETIC FIELDS ON THE PROPERTIES OF AMORPHOUS CARBON PREPARED BY PLASMA DEPOSITION R.H. Jarman and A.T. Howe	273
X-RAY PHOTOEMISSION STUDY OF SILICON NITRIDE-GaAs INTERFACES IN RELATION WITH GaAs MESFET PASSIVATION Patrick Alnot, J. Olivier, F. Wyczisk, J.F. Peray, and R. Joubart	279
BONDED HYDROGEN IN SILICON OXIDE THIN FILMS DEPOSITED BY REMOTE PLASMA ENHANCED CHEMICAL VAPOR DEPOSITION D.V. Tsu and G. Lucovsky	285
DEPOSITION OF a-Ge:H BY GeF_4/H_2 GLOW DISCHARGE D. Slobodin, S. Aljishi, and S. Wagner	291

MEASUREMENT OF PLASMA ETCH-INDUCED DAMAGE TO SILICON BENEATH SiO ₂ LAYER: EFFECTIVE RANGE OF PLASMA ETCH DAMAGE THROUGH SiO ₂ W. Lee Smith and I-Wen Huang Connick	299
GATE OXIDE DAMAGE IN DRY PHOTORESIST STRIPPING ENVIRONMENTS Karen H. Sibbett, J. Ignacio Ulacia, James P. McVittie, and Richard F. Reichelderfer	307
HIGH QUALITY DEPOSITION OF SiO ₂ DOWNSTREAM FROM A MICROWAVE DISCHARGE B. Robinson, P.D. Hoh, P. Madakson, T.N. Nguyen, and S.A. Shivashankar	313
THE EFFECTS OF MODULATION ON AN RF DISCHARGE IN SILANE AND ON THE DEPOSITED a-Si:H L.J. Overzet, J.T. Verdeyen, R.M. Roth, and F.F. Carasco	321
THE RELATIONSHIP BETWEEN EMISSION SPECTROSCOPY AND OPTICAL PROPERTIES OF AMORPHOUS CARBON FILMS Richard M. Roth and Richard H. Jarman	327
PART IV: THERMAL PLASMAS	
*PLASMA PROCESS ROUTES TO SYNTHESIS OF CARBIDE, BORIDE AND NITRIDE CERAMIC POWDERS Aaron J. Becker, Thomas N. Meyer, Frances N. Smith, and Jon F. Edd	335
PLASMA DEPOSITED Ni-Al-Mo METAL-METAL COMPOSITES M.R. Jackson and P.A. Siemers	347
STABILITY STUDIES OF PLASMA SPRAYED ZIRCONIA Harry E. Eaton and Richard C. Novak	353
REDUCTION OF SELECTED METAL OXIDES IN A THERMAL PLASMA PRODUCED BY A NONTRANSFERRED ARC TORCH Brent A. Detering, James A. Batdorf, and Chien M. Wai	359
PLASMA STUDIES IN VACUUM ARC REMELTING Rodney L. Williamson, Frank J. Zanner, Lee A. Bertram, and Henry C. Peebles	365
THE EFFECTS OF GAS COMPOSITION AND PRESSURE ON RF PLASMA SINTERING OF MgO Peter C. Kong, Y.C. Lau, and E. Pfender	371
Beta-SiC SYNTHESIS IN A THERMAL ARGON PLASMA JET REACTOR Peter C. Kong and E. Pfender	377
*MATERIALS SYNTHESIS Peter R. Strutt and Julian P. Partridge	385
*Invited Paper	

THERMAL REDUCTION OF ILMENITE CONCENTRATES IN A DC TRANSFERRED-ARC PLASMA FURNACE A.D. Brent and K.J. Reid	399
ADVANCED POWDER FEEDING DEVICE FOR USE IN GAS/SOLID PLASMA SYNTHESIS AND PROCESSING APPLICATIONS F.W. Giacobbe	405
DESIGN AND COMMISSIONING OF A CONTINUOUS TRANSFERRED ARC PLASMA MELTER FOR THE VITRIFICATION OF NUCLEAR WASTE R.J. Munz and G.Q. Chen	417
HIGH POWER GLOW DISCHARGE USING GAS INJECTION MULTIPLE POROUS ELECTRODES J.E. Harry and D.R. Evans	425
AUTHOR INDEX	431
SUBJECT INDEX	433